



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Patent Application of:

Sanjay S. Natarajan, et al.

Serial No. 09/750,734

Filed: December 27, 2000

For: **MULTI-LAYER FILM STACK FOR
EXTINCTION OF SUBSTRATE
REFLECTIONS DURING PATTERNING**

Examiner: Gurley, Lynne Ann

Art Unit: 2812

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REC'D
NOV 13 2002
TC 2800 MAIL ROOM

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AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION

Box AF - FEE
Commissioner for Patents
Washington, D.C. 20231-9998

Dear Sir:

In response to an Office Action having a mailing date of October 2, 2002, please amend the above-identified patent application as follows.

11/15/2002 J WILLIA1 00000006 022666 09750734

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IN THE CLAIMS

Please amend the claims as follows:

Subj > 1. (Amended) A method comprising:

introducing an etch stop layer over a substrate;

*introducing a dielectric layer over the etch stop layer between an
interconnection line and a contact point on the substrate, the dielectric layer
comprising a plurality of different material layers, wherein each respective*

11/15/2002 A YONDAF1 00000083 09750734

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App/No.: 09/750,734
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